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**TRANSMITTAL MESSAGE/COVER SHEET**

Date: January 21, 2000

**PLEASE DELIVER THE FOLLOWING PAGES TO:**

Name: Examiner G. Cantelmo

Company/Firm: U.S. Patent and Trademark Office

Fax No.: 703-305-6078

Pages: (including this sheet) - 11

Re: U.S. Patent Appln. No. 08/902,331  
Filed: July 29, 1997 - Title: Magnetron Atomization Source  
And Method of Use  
Our Ref. 622/42052DV

From: James F. McKeown

Firm: Evenson, McKeown, Edwards & Lenahan, P.L.L.C.

Fax No.: (202) 628-8844

MESSAGE: Attached is a proposed After-Final Response. Please advise if you have any objections or changes. Jim McKeown

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**DRAFT**Attorney Docket: 622/42052DV  
PATENTIN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: PIUS GRUENENFELDER ET AL.

Serial No.: 08/902,331 Group Art Unit: 1753

Filed: JULY 29, 1997 Examiner: Cantelmo, G.

Title: MAGNETRON ATOMIZATION SOURCE  
AND METHOD OF USE**AFTER-FINAL RESPONSE  
EXPEDITED HANDLING REQUESTED**VIA FACSIMILE - 703-305-6078Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

The following is responsive to the Office Action mailed  
April 9, 1999.

IN THE SPECIFICATION

Page 10, between lines 14 and 15 insert the following  
paragraph.

--The above-described relationship between  $d_{13}$  (the maximal  
distance of the new atomization surface to the disk surface to  
be coated) and  $r_{13}$  (the radius of the circular workpiece disk)  
allow a target taper to be defined by the difference between  $D_{112}$   
and the distance  $a_1$  which represents the distance spanned by an  
interior surface  $F_q$ , i.e.  $co = d_{13} - a_1$ . The disclosed relationship  
and the upper and lower values of  $d_c$  can thus be represented by  
the following:

$$0.2\phi_{13} \leq d_{13} \leq 0.5\phi_{13}$$

(1)